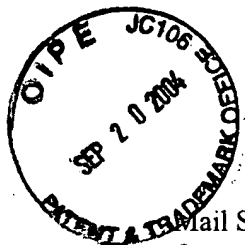


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IFW



September __, 2004

Mail Stop Amendment
Commissioner For Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Applicant(s): Timothy R. Piwonka-Corle
Title: Focused Beam Spectroscopic Ellipsometry Method And System
Application No.: 10/716,805 Filing Date: November 18, 2003
Examiner: Rossenberger, R.A. Group Art Unit: 2877
Docket No.: TNCR.059US6 Conf. No.: 8189

Dear Sir:

Transmitted herewith are the following documents in the above-identified application:

- (1) Return Receipt Postcard;
- (2) This Transmittal Letter (1 page)
- (3) Information Disclosure Statement (2 pages);
- (4) PTO Form 1449 (14 sheets); and
- (5) Check for \$180.00.

Please charge any additional fees required and credit any overpayment to our
Deposit Account No. 502664.

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22313-1450, on September 17, 2004.

Franklin Dyer

Respectfully submitted,

James S. Hsue
Reg. No. 29,545

Date

9/17/04



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Timothy R. Piwonka-Corle
Title: Focused Beam Spectroscopic Ellipsometry Method And System
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Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Pursuant to 37 C.F.R. §§ 1.56, 1.97 and 1.98, Applicant(s) call(s) the documents listed on the enclosed Form PTO-1449 and copies filed herewith to the Examiner's attention in this patent application.

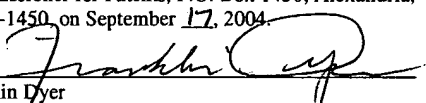
This application has a filing date after June 30, 2003. Copies of the U.S. Patent(s) and U.S. Published Patent Application(s) documents listed on the accompanying Form PTO-1449 are not enclosed. Copies of the documents listed on the accompanying Form PTO-1449 that are not enclosed were previously submitted in Application No. 09/248,876, from which this Application claims an earlier effective filing date.

Citation of these documents shall not be construed as (1) an admission that the documents are prior art with respect to the invention or inventions claimed in this application, (2) a representation that a search has been made (other than as indicated by any cited document), or (3) an admission that the cited information is, or is considered to be, material to patentability as defined in § 1.56(b).

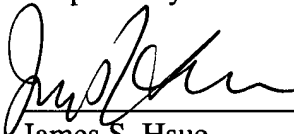
Attorney Docket No.: TNCR.059US6

Application No.: 10/716,805

This information disclosure statement is submitted under 37 C.F.R. § 1.97(c). A check including \$180.00 for the information disclosure statement fee under 37 C.F.R. § 1.17(p), is enclosed. The Commissioner is authorized, however, to charge any fee that may be required, or to credit any overpayment, against Deposit Account No. 502664. This form is being submitted in duplicate.

<p align="center"><u>Certificate of Mailing Under 37 CFR 1.8</u></p> <p>I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope address to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on September 17, 2004.</p> <p> Franklin Dyer</p>

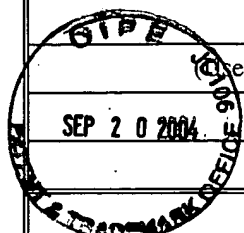
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	2	4,645,349	2/1987	Tabata			
	3	4,653,908	3/1987	Yajima et al.			
	4	4,653,924	03/31/87	Itonaga et al.			
	5	4,655,595	04/07/87	Bjork et al.			
	6	4,672,196	06/09/87	Canino			
	7	4,692,024	09/08/87	Bloss			
	8	4,790,659	12/1988	Erman et al.			
	9	4,810,872	3/7/89	Murakoshi et al.			

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		Document	Date	Country	Class	Subclass	Yes	No
	10	EP652415A1	5/10/9S	Europe				
	11	11342936	5/25/89	Japan			Yes	
	12	2602338A	2/5/88	France			Yes	
	13	63500263	1/28/88	Japan			Abstract	
	14	6332338	2/12/88	Japan			Abstract	
	15	63243836	10/11/88	Japan			Abstract	
	16	2126106	5/15/90	Japan			Abstract	
	17	1132935	5/25/89	Japan			Yes	
	18	214057	1/29/90	Japan			Yes	
	19	2118247	9/21/90	Japan			Abstract	

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	20	4,834,539	05/30/89	Le Bris et al.			
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	25	5,076,696	12/31/91	Cohn et al.			
	26	5,091,320	02/25/1992	Aspnes et al.			
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	29	2297008	7/12/90	Japan			Abstract	
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	31	4340404	11/26/92	Japan			Abstract	
	32	5264355	10/12/93	Japan			Abstract	
	33	5296841	11/12/93	Japan			Abstract	
	34	6341952	12/13/94	Japan			Abstract	
	35	7198342	8/1/95	Japan			Abstract	
	36	8500432	1/16/96	Japan			Abstract	
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	38	SU987410	5/18/81	U.S.S.R.			Abstract	

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	39	5,166,752	11/24/92	Spanier et al.			
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	42	5,208,451	05/04/1993	Deck			
	43	5,237,167	08/17/1993	Hibbard			
	44	5,251,007	10/1993	Rinke			
	45	5,262,845	11/16/93	Milosevic et al.			
	46	5,294,289	3/15/94	Heinz et al.			
	47	5,307,210	4/26/94	MacFarlane et al.			

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		Document	Date	Country	Class	Subclass	Yes	No
	48	SU1288558A1	4/20/83	U.S.S.R.			Abstract	
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	50	SU1140009A	7/18/83	U.S.S.R.			Abstract	
	51	SU1141297A	10/18/83	U.S.S.R.			Abstract	
	52	SU1157416A	12/26/83	U.S.S.R.			Abstract	
	53	SU1260697A1	7/4/84	U.S.S.R.			Abstract	
	54	SU1369471A	2/28/86	U.S.S.R.			Abstract	
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	57	SU1695145A1	8/3/88	U.S.S.R.			Abstract	

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	62	5,450,201	9/12/95	Katzir et al.			
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		Document	Date	Country	Class	Subclass	Yes	No

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	67	"A broadband UV small spot spectroscopic ellipsometer," T.R. Corle et al., <i>Proceedings of SPIE - The International Society for Optical Engineering, Integrated Circuit Metrology, Inspection, and Process Control IX</i> . Vol. 2439, February 1995, pp. 114-125.
	68	"A combined spectroscopic ellipsometer and spectrophotometer," J.J. Estabil et al., <i>Solid State Technology</i> , Vol. 38, No. 4, April 1995, pp. 71-72.
	69	"A double polarization modulation far-infrared spectrometer," V.M. Da Costa et al., <i>Rev. Sci. Instrum.</i> , Vol. 61, No. 8, August 1990, pp. 2113-2120.

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		Document	Date	Country	Class	Subclass	Yes	No
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	80	"A Method for Measuring Infrared Reflection-Absorption Spectra of Molecules Adsorbed on Low-Area Surfaces at Monolayer and Submonolayer Concentrations," W.G. Golden et al., <i>Journal of Catalysis</i> , Vol. 71. 1981. pp. 395-404.						
	81	"A New Micro Spectroscopic Ellipsometer for On Line Control in Silicon Industry Developed for Tencor Prometrix," J.L. Stehle et al., WISE '95 Workshop International on Spectroscopic Ellipsometry," February 1995.						
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	83	"A reflectance anisotropy spectrometer for real-time measurements," O. Archer et al., <i>Rev. Sci. Instrum.</i> , 63(11), November 1992, pages 5332-5339.	
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	86	"An Ellipsometry System for High Accuracy Metrology of Thin Films," G.A. Candela et al., <i>Proceedings of SPIE-The International Society for Optical Engineering, Integrated Circuit Metrology II</i> , Vol. 480, 1984, pp. 2-8.	
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	90	"Anomalous behavior of density and mechanical properties of thermosetting polymers with increasing conversion," K.P. Pang, Ph.D. Dissertation, January 1989, pp. 1-203.	
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	93	"Applications of IR Ellipsometric Spectroscopy to Surface Studies," J.D. Fedyk et al., <i>Surface Science</i> , Vol.89, 1879, pp. 404-424.	
	94	"Applications of the Theory of Optical Spectroscopy to Numerical Simulations," M. Milosevic et al., <i>Applied Spectroscopy</i> , Vol. 47, No. 5, 1993, pp. 566-574.	
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	101	"Characterization of the accretion of material by microparticles using resonant ellipsometry," L.M. Folan, <i>Applied Optics</i> , Vol. 31, No. 12, April 20, 1992, pp. 2066-2071.	
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	105	"Complete measurement of Kerr parameters by using rotating analyzer magneto-optic spectroscopy," L-Y. Chen et al., <i>Proceedings of SPIE-The International Society for Optical Engineering, Polarization Analysis and Measurement</i> , Vol. 1746, 1992, pp. 307-315.	
	106	"Considerations in building a low-noise reflection absorption infrared spectrometer," J.B. Benziger et al., <i>Applied Optics</i> , Vol. 26, No. 2, January 15, 1987, pp. 343-350.	
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	113	"Electronic states and thicknesses of GaAs/GaAl As quantum wells as measured by electroreflectance and spectroscopic ellipsometry," M. Erman et al., <i>J. Appl. Phys.</i> , Vol. 56, No. 11, December 1, 1984, pp. 3241-3249.	
	114	"Ellipsometric Investigation of Transition Layer Heterostructures," S.A. Titov et al., <i>Instruments and Experimental Techniques</i> , Vol. 37, No. 4, Part 2, July-August 1994, pp. 475-478.	
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	119	"Experimental aspects of attenuated total reflectance spectroscopy in the infrared," V. Offermann et al., <i>Vibrational Spectroscopy</i> , Vol. 8, 1995, pp. 135-140.	
	120	"Extension of Ellipsometry to the Case of High-Reflectance Small Samples and Long-Wavelength Radiation," A.B. Sushkov et al., <i>Optics and Spectroscopy</i> , Vol. 76, No. 3, March 1994, pp. 407-413.	
	121	"Extension of spectroscopic ellipsometry to the far infrared," G. Dittmar et al., <i>Thin Solid Films</i> , Vol. 234, Nos. 1-2, 1993, pp. 346-351.	
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	123	"Far-IR spectroscopic ellipsometer," K.-L. Barth et al., <i>Thin Solid Films</i> , Vol. 234, 1993, pp. 314-317.	
	124	"Fast polarization modulated ellipsometer using a microprocessor system for digital Fourier analysis," B. Drevillon et al., <i>Rev. Sci., Instrum.</i> , Vol. 53, No. 7, July 1982, pp. 969-977.	
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